

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of

Hisao HAYASHI et al

Appln. No. 09/772,986

Filed: January 31, 2001

For: THIN FILM SEMICONDUCTOR

DEVICE, DISPLAY DEVICE USING)

SUCH THIN FILM SEMI
CONDUCTOR DEVICE AND

MANUFACTURING METHOD

Group Art Unit: 2811

Examiner: Tran, Thien F.

BOX NON-FEE AMENDMENT Commissioner of Patents Washington, D.C. 20231

THEREOF

SUPPLEMENTAL RESPONSE

Sir:

In addition to the amendment and response filed on August 8, 2002, responsive to the non-final Office Action dated May 8, 2002, please consider the remarks set forth below.

REMARKS

Applicant now provides a full translation of the Examiner's cited reference Hisao et al (JP 10209467). Applicant requests reconsideration of the claims in view of the text of the cited reference and the following remarks.

35 USC § 103 Rejection

The Examiner rejects Claims 1-8 under 35 USC §103 as being unpatentable over Hisao et al (JP 10209467). The Examiner states that Hisao discloses a gate electrode having a thickness of about 100 nm which could be more or less than 100 nm. The Examiner states that because the general conditions of the claim are disclosed, it would be obvious to one of ordinary skill in the art to modify Hisao to the less than 100 nm range.